

AMENDMENTS TO THE ABSTRACT:

Please amend the Abstract as follows:

A method for creating mask pattern data for fabricating a circuit includes the steps of dividing original mask pattern data into a plurality of regions having a first size; performing OPC on the plurality of regions and creating first mask pattern data based on the plurality of processed regions; dividing the original mask pattern data into a plurality of regions having a second size; performing OPC on the plurality of regions and creating second mask pattern data based on the plurality of processed regions; and when no non-matching data is present as a result of matching comparison, setting the first or second mask pattern data as the mask pattern data for fabricating the circuit; and when non-matching data is present as a result of the comparison, deleting the non-matching data from the first or second mask pattern data so as to create the mask pattern data for fabricating the circuit.